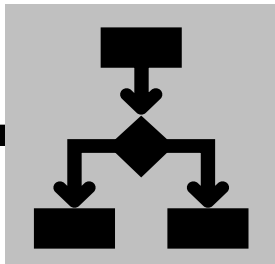
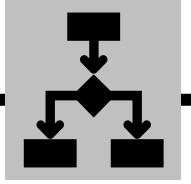




Using **L-2L Method** for De-embedding Structure on the **PCB level**



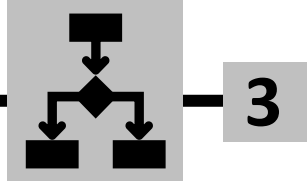
Outline



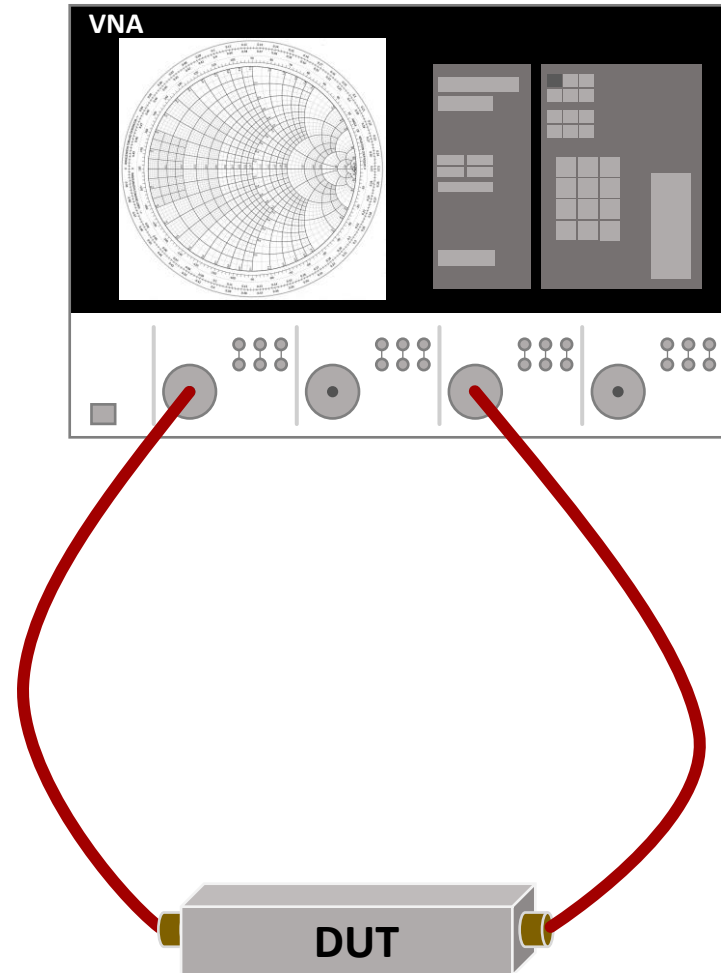
2

- ☐ Understanding De-embedding
- ☐ Why De-embedding methods is important?
- ☐ Introduction of De-embedding Methods
- ☐ Theoretical View of L-2L Method
 - Through de-embedding
 - Results
 - Weaknesses
- ☐ Introduction of 2x Thru De-embedding
 - TDR and Time gating method
 - Results
 - Weaknesses
- ☐ How to use the L-2L method for PCB structures
- ☐ The Structures That Can be De-embedded with this method
 - Advantage
 - Weaknesses
- ☐ Conclusion
- ☐ Future work
- ☐ References

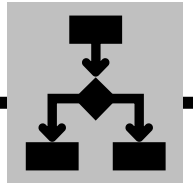
Understanding De-embedding



- Standard **RF cables** are used to **connect** the ports of **the VNA** to **the DUT**.

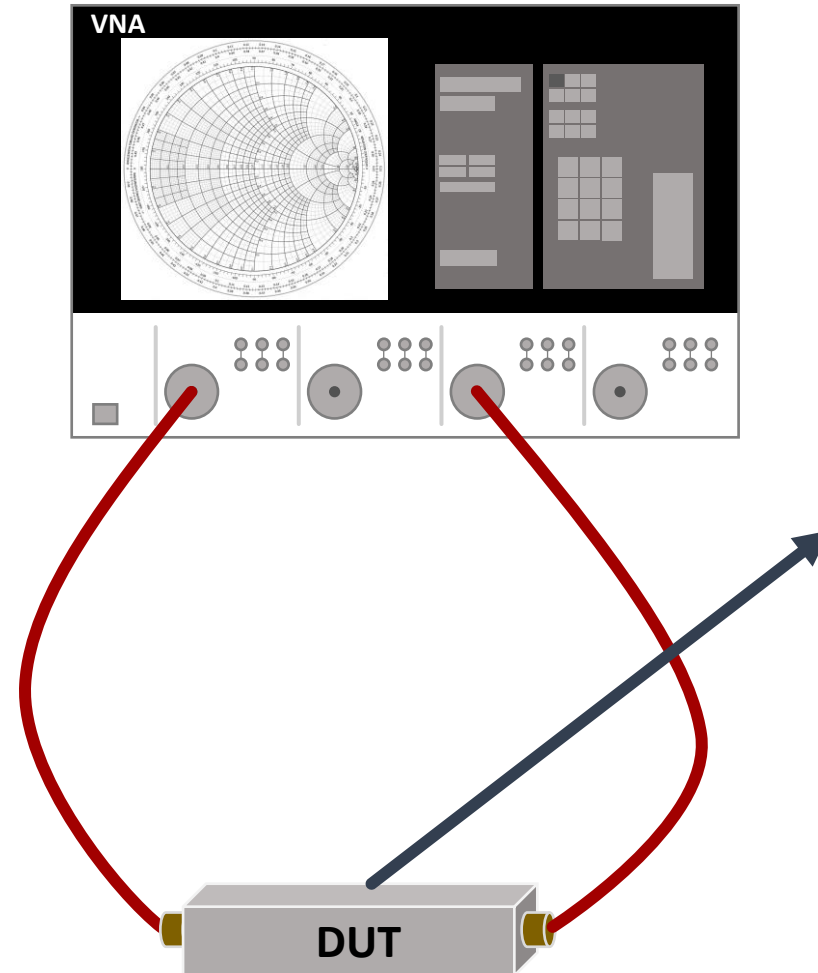


Understanding De-embedding

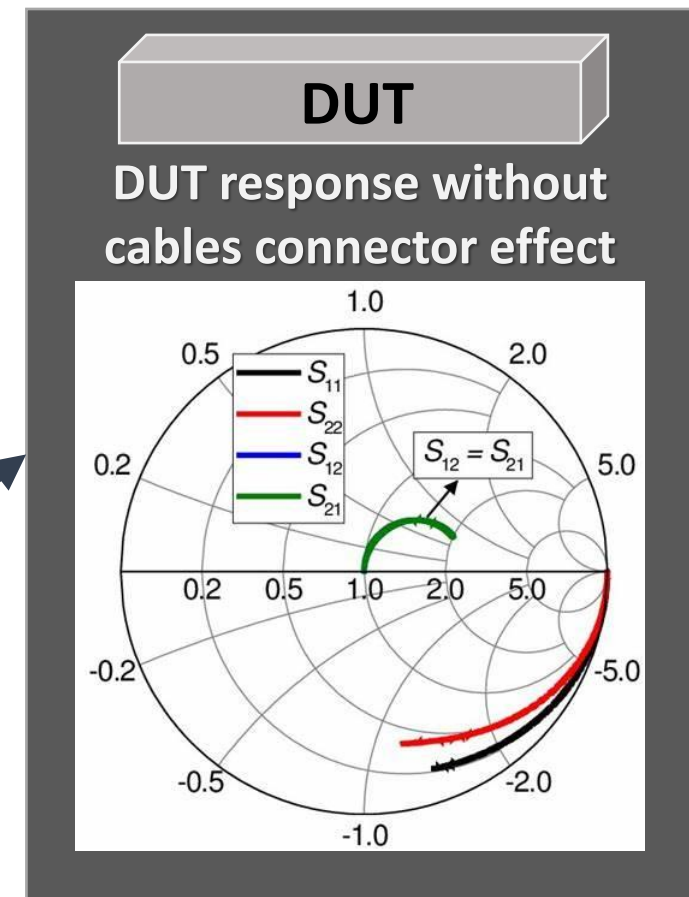


4

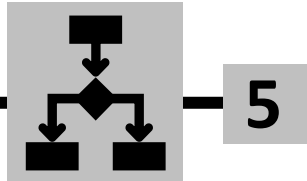
- ❑ Standard **RF cables** are used to **connect** the ports of **the VNA** to the **DUT**.
- ❑ By **calibrating/de-embedding** at the end of these **cables can be removed**.
- ❑ Standard **calibration** methods:
 - TRL
 - SOLT
 - LRL
 - **2x Thru**



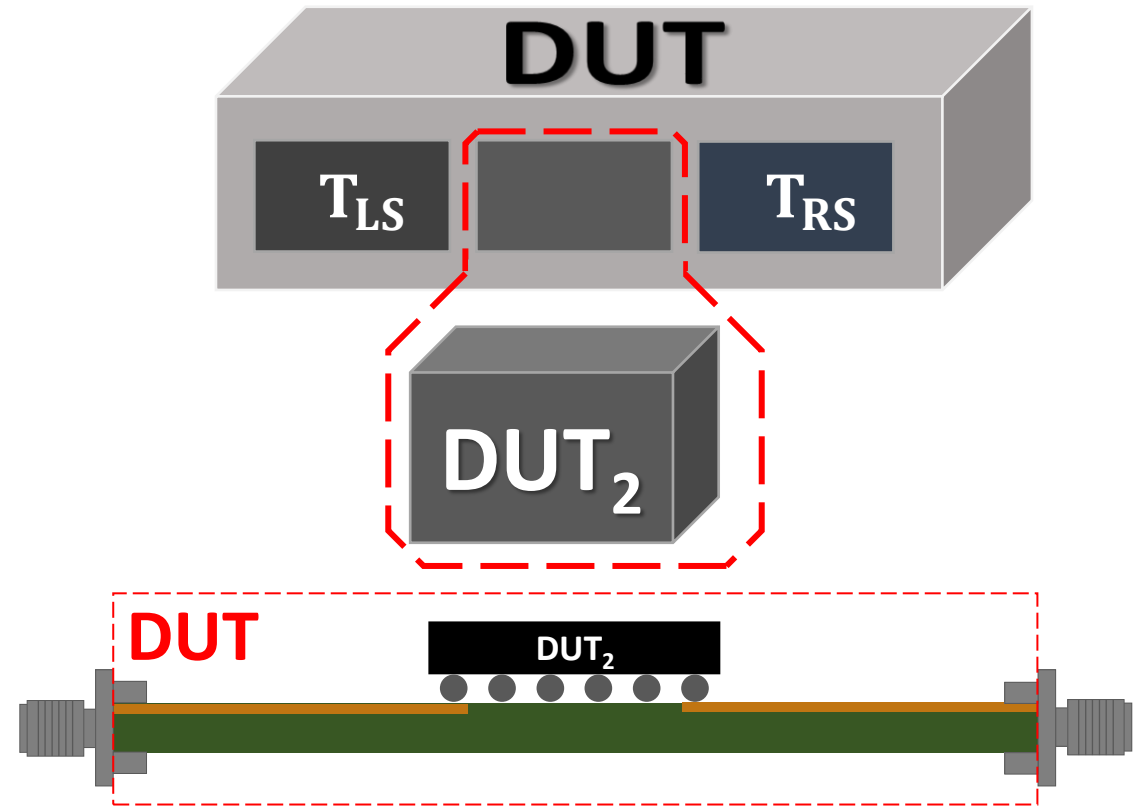
By Calibration



Why De-embedding methods is important?



- ❖ The extreme importance of accurate parasitic de-embedding techniques to RF device characterization has already been established.
- ❖ In general, the parasitic contributions of device-under-test (DUT) structures mainly arise from **probe pads**, the **interconnection lines** connected to the intrinsic on-chip DUT structure.
- ❖ The most important purpose of **mathematical-based de-embedding** is to **access the inside of the DUT**.

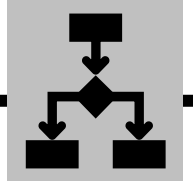


$$\mathbf{T}_{DUT} = [\mathbf{T}_{LS}] \times [\mathbf{T}_{DUT_2}] \times [\mathbf{T}_{RS}]$$

$$\mathbf{T}_{DUT_2} = [\mathbf{T}_{LS}]^{-1} \times [\mathbf{T}_{DUT}] \times [\mathbf{T}_{LR}]^{-1}$$

“Mike Resso: Senior engineer in the Keysight company, **Author of Signal Integrity Characterization Techniques**, 2019”

Introduction of De-embedding Methods



6

❖ De-embedding techniques can be classified as three groups:

- ❑ The first group is called the **lumped equivalent circuit model based** technique for short DUT structures:

The largest dimension of the structure $< 0.1 \lambda$

- Open method
- Open-Short method
- Vandamme method

- ❑ The second group is called the **cascade based with lumped equivalent circuit model based** technique for short DUT structures:

The largest dimension of the structure $< 0.1 \lambda$

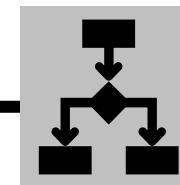
- **L-2L method**
- LiLj method
- Hybrid method

- ❑ The third group is called the **cascade based** technique for large DUT structures:

The largest dimension of the structure $> 0.1 \lambda$

- TRL
- **2X Thru**
- 1X Fixture

Theoretical View of L-2L Method



7

L-2L:

For the L-2L de-embedding method, the **measurement of two transmission lines is required**. The first transmission line is of **length L**, and the second transmission line is of **length 2L**. **Pads are assumed to be symmetric.**

$$\mathbf{T}_{\text{meas}_L} = [\mathbf{T}_{LS}] \times [\mathbf{T}_L] \times [\mathbf{T}_{RS}]$$

\mathbf{T}_{LS} : Represent the matrix of the left pad;

$$\mathbf{T}_{\text{meas}_{2L}} = [\mathbf{T}_{LS}] \times [\mathbf{T}_{2L}] \times [\mathbf{T}_{RS}]$$

$\mathbf{T}_{L\&2L}$: Represent the matrix of the lines;

\mathbf{T}_{RS} : Represent the matrix of the right pad;

$$\mathbf{T}_{\text{thru}} = [\mathbf{T}_{\text{meas}_L}] \times [\mathbf{T}_{\text{meas}_{2L}}]^{-1} \times [\mathbf{T}_{\text{meas}_L}] =$$

$$T_{LS} \times T_L \times T_{RS} \times T_{RS}^{-1} \times T_L^{-1} \times T_L^{-1} \times T_{LS}^{-1} \times T_{LS} \times T_L \times T_{RS}$$

$$= [\mathbf{T}_{LS}] \times [\mathbf{T}_{RS}]$$

$$\mathbf{T}_{2L} = [\mathbf{T}_{LS}]^{-1} \times [\mathbf{T}_{\text{meas}_{2L}}] \times [\mathbf{T}_{LR}]^{-1}$$

$$\mathbf{T} = \begin{bmatrix} T_{11} & T_{12} \\ T_{21} & T_{22} \end{bmatrix}$$

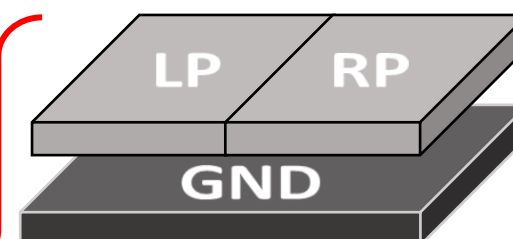
$$\mathbf{S} = \begin{bmatrix} S_{11} & S_{12} \\ S_{21} & S_{22} \end{bmatrix}$$

$$\begin{aligned} T_{11} &= \frac{1}{S_{21}} \\ T_{12} &= \frac{-S_{22}}{S_{21}} \\ T_{21} &= \frac{-S_{11}}{S_{21}} \\ T_{22} &= \frac{S_{12}S_{21} - S_{11}S_{22}}{S_{21}} \end{aligned}$$

$$\begin{aligned} S_{11} &= \frac{T_{21}}{T_{11}} \\ S_{12} &= \frac{T_{11}T_{22} - T_{12}T_{21}}{T_{11}} \\ S_{21} &= \frac{1}{T_{11}} \\ S_{22} &= \frac{-T_{12}}{T_{11}} \end{aligned}$$

$$\begin{aligned} A &= B \times C \times D \\ A^{-1} &= D^{-1} \times C^{-1} \times B^{-1} \\ A \times A^{-1} &= U \\ U \times A &= A \\ U &= \begin{bmatrix} 1 & 0 \\ 0 & 1 \end{bmatrix} \end{aligned}$$

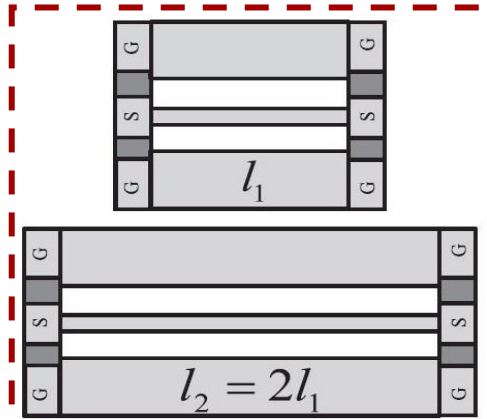
[3] Ref: Conversions between S, Z, Y, H, ABCD, and T parameters which are valid for complex source and load impedances



π - Model

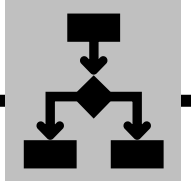
T - Model

Calibration-kit



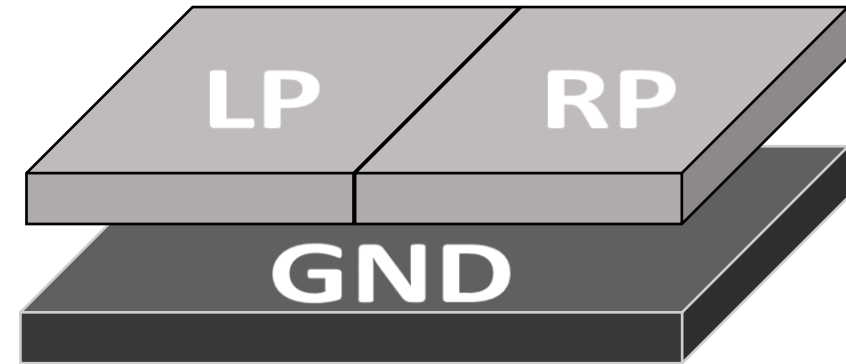
[2] Ref: De-embedding techniques for transmission lines: An exploration, review, and proposal, 2013

Separation of $[T_{LS}]$ and $[T_{RS}]$ from T_{thru}



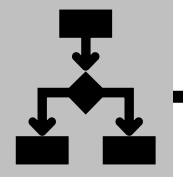
8

$$T_{\text{thru}} = [T_{LS}] \times [T_{RS}]$$



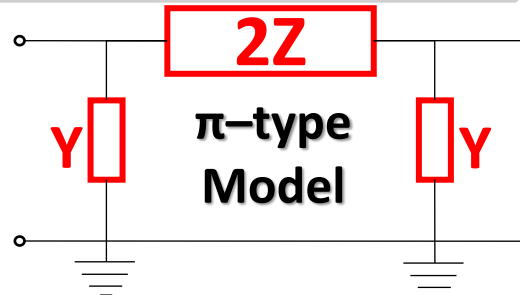
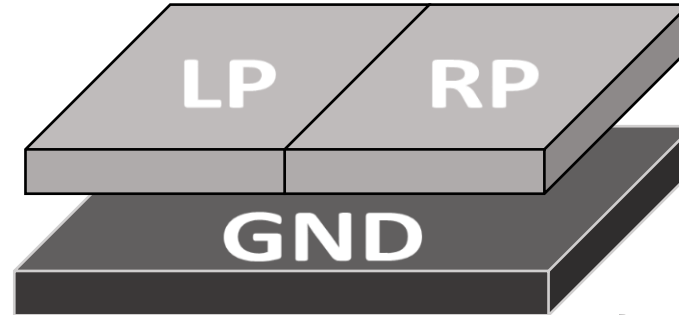
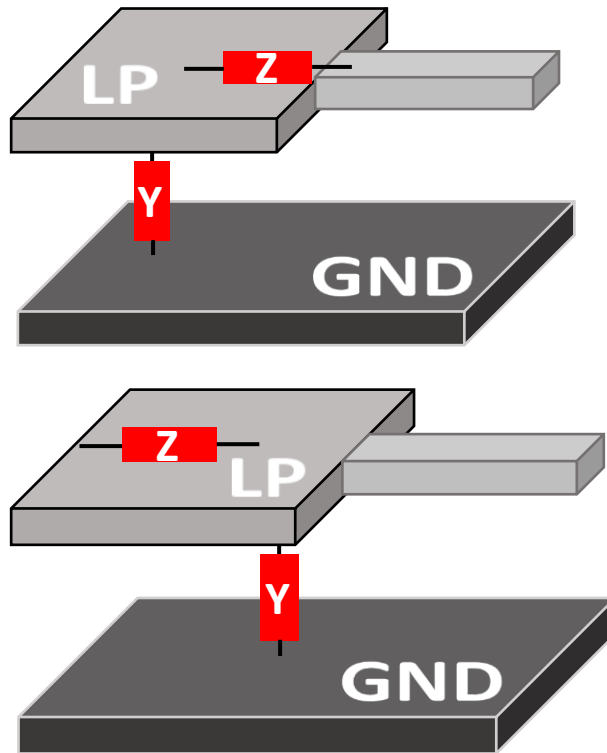
Small Scale

Separation of $[T_{LS}]$ and $[T_{RS}]$ from T_{thru} (Through-Only method)

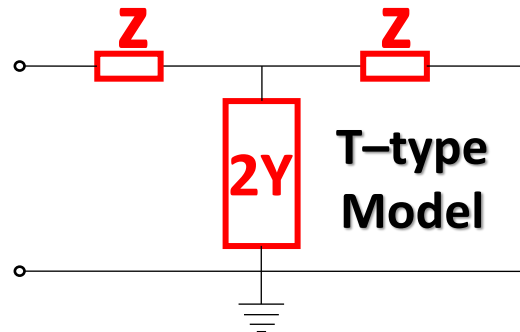


9

$$T_{thru} = [T_{LS}] \times [T_{RS}]$$



[5] Ref: Jiming Song, Feng Ling, G. Flynn, W. Blood and E. Demircan, "A de-embedding technique for interconnects," 2001



[6] Ref: S. Kawai, K. K. Tokgoz, K. Okada and A. Matsuzawa, "L-2L de-embedding method with double-T-type PAD model for millimeter-wave amplifier design," 2015

Original L-2L

$$[T_{LS}] = [T_{RS}] = \sqrt{T_{Thru}}$$

The pad is modeled with a capacitor

[4] Ref: Rautio, J.C. (1991). A de-embedding algorithm for electromagnetics. *International Journal of Microwave and Millimeter-wave Computer-aided Engineering*

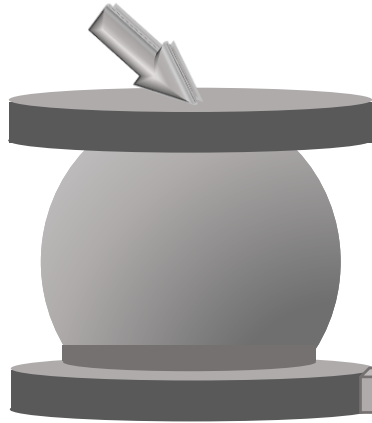
Lumped Elements

$$Z = j\omega L + R$$

$$Y = j\omega C + G$$

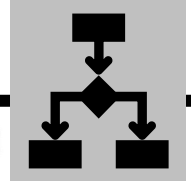
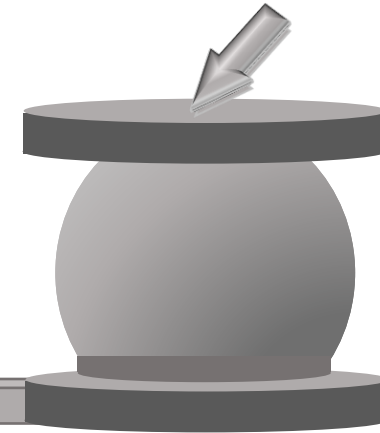
The L-2L De-embedding Results

Probe 1

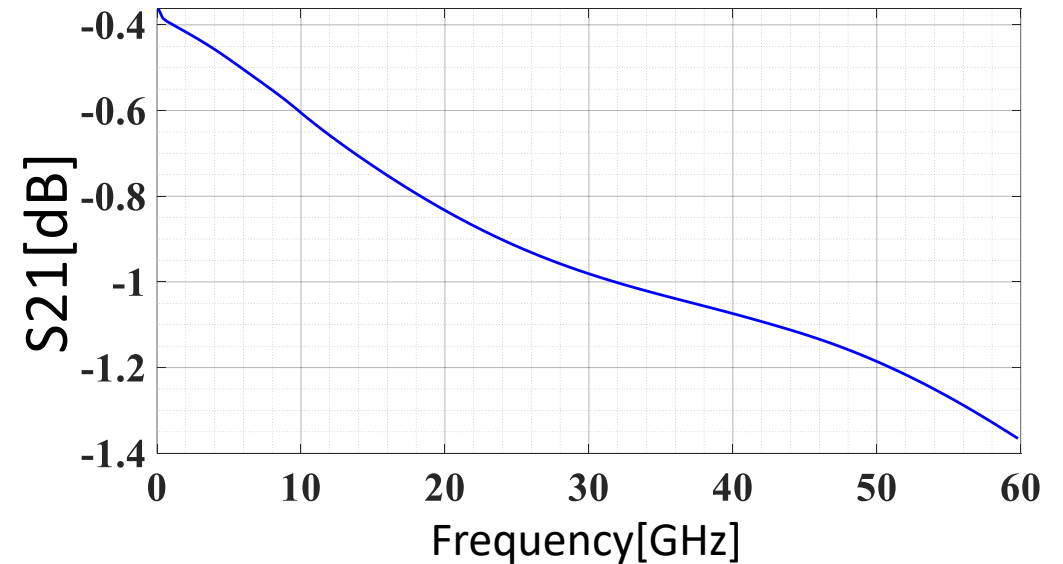
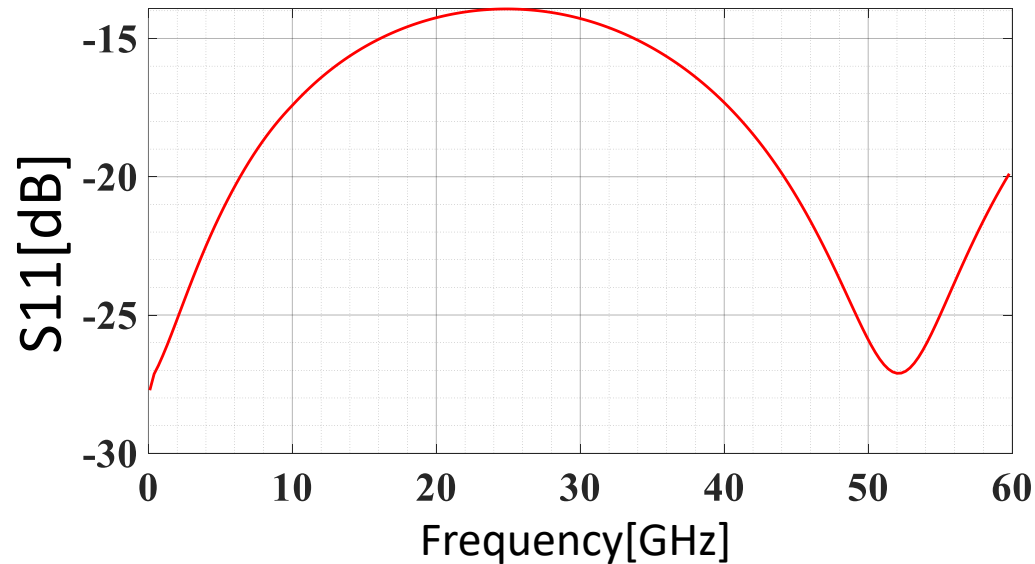


Silicon Interposer

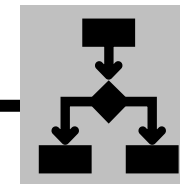
Probe 2



10

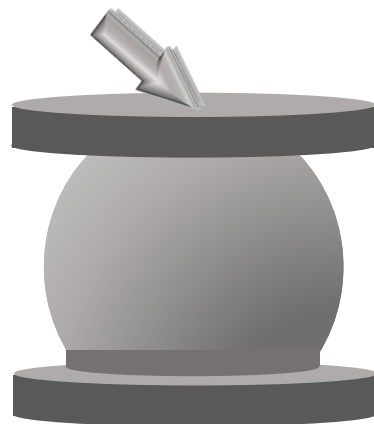


The L-2L De-embedding Results

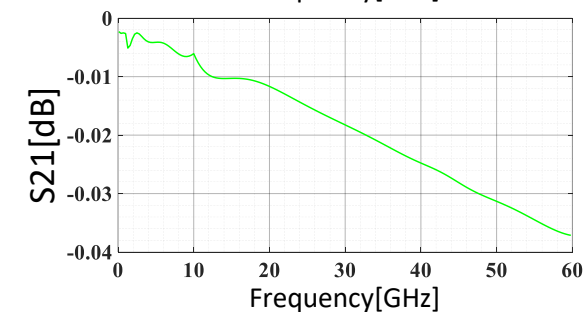
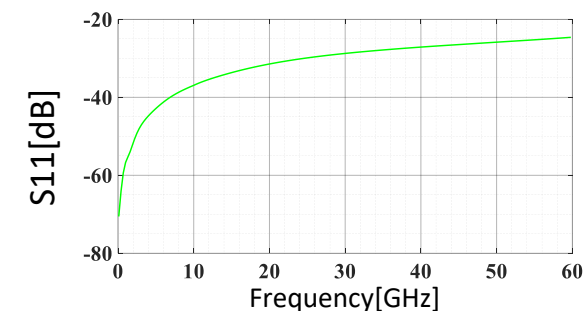
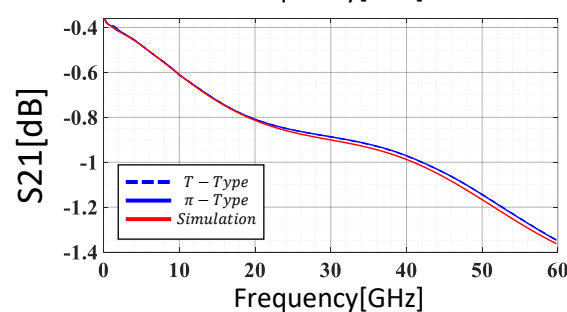
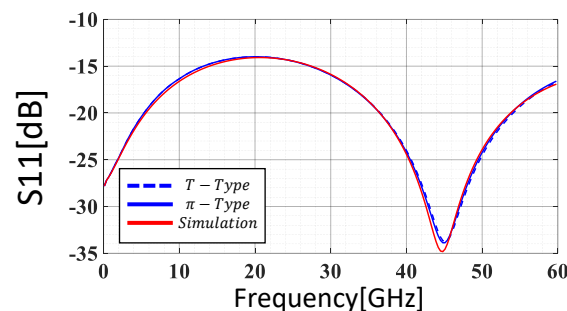
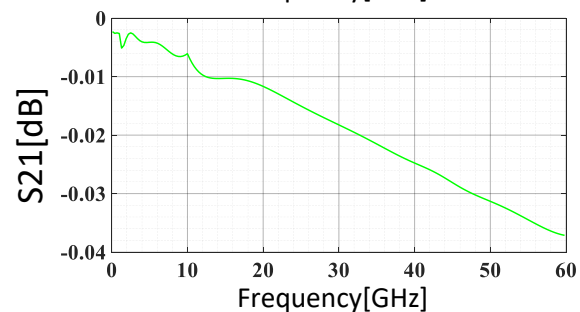
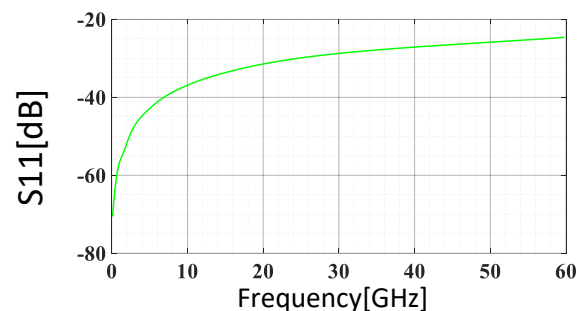
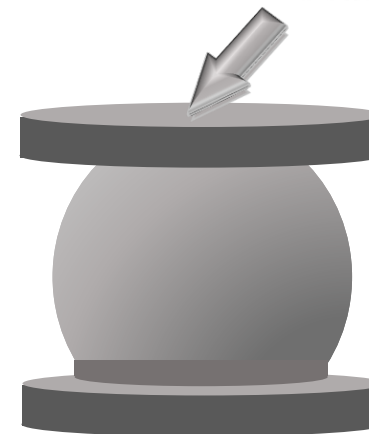


11

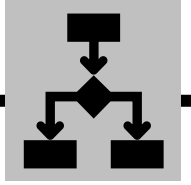
Probe 1



Probe 2



The weaknesses of L-2L Method

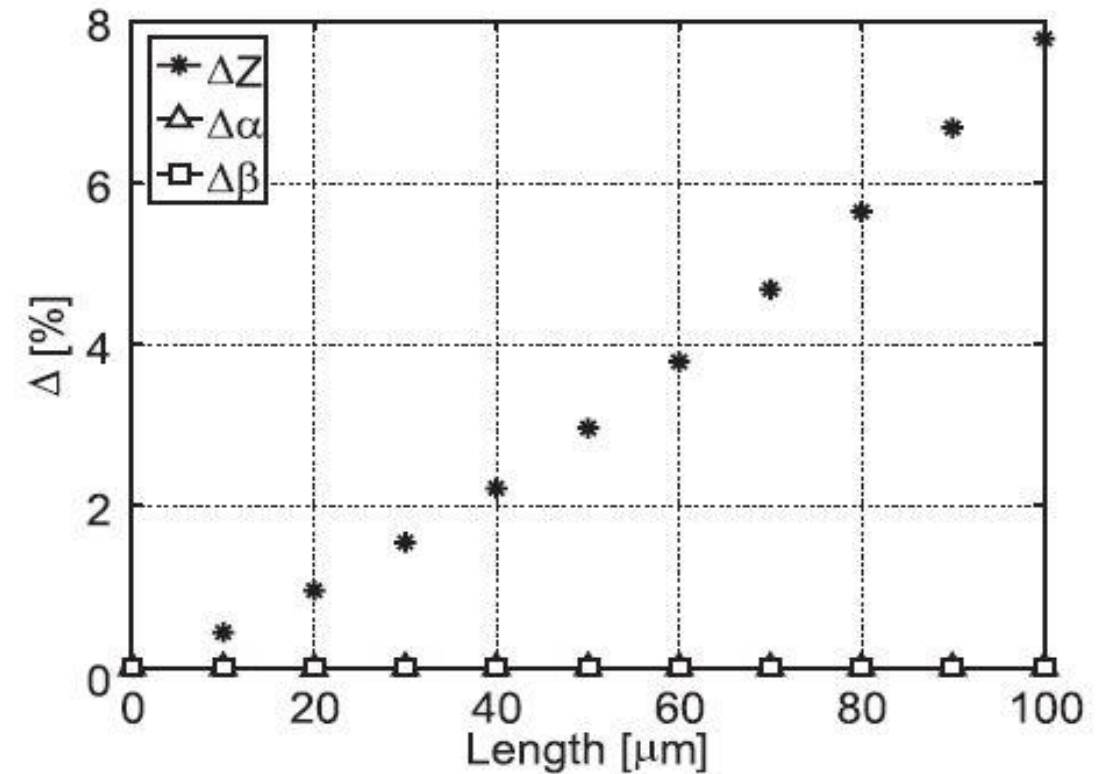


12

- By using the measured S-Parameter the parasites of the pad can be calculated which is modeled as a **π -type** or **T-type** lumped constant circuit. However, in **through-only** method, **the length of the through-line is required to be very short** to match with the π -type lumped model.

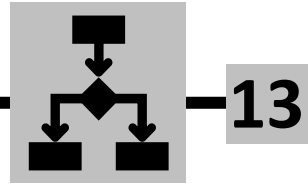
$$\Delta = \left| \frac{X^{L-2L} - X^L}{X^L} \right|$$

- The parasitic contribution of the extra grounded metal strip **cannot be ignored** if the frequencies are high or if the device under test (DUT) structures are large.



[8] Ref: Ning Li, "Evaluation of a Multi-Line De-Embedding Technique up to 110 GHz for Millimeter-Wave CMOS Circuit Design", February 2010 IEICE Transactions

Introduction of 2x Thru De-embedding



13

2X Thru:

The S11 left and right fixtures are calculated from the **time domain reflectometry (TDR)**, while the S21 and S22 fixtures are obtained from the wave peeling algorithm. **Only a 2X thru pattern is needed.**

- Symmetry in the 2x Thru is assumed.
- **Minimum spacing between discontinuities in the 2x Thru is needed.**

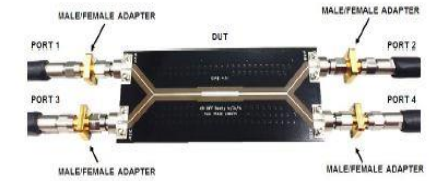
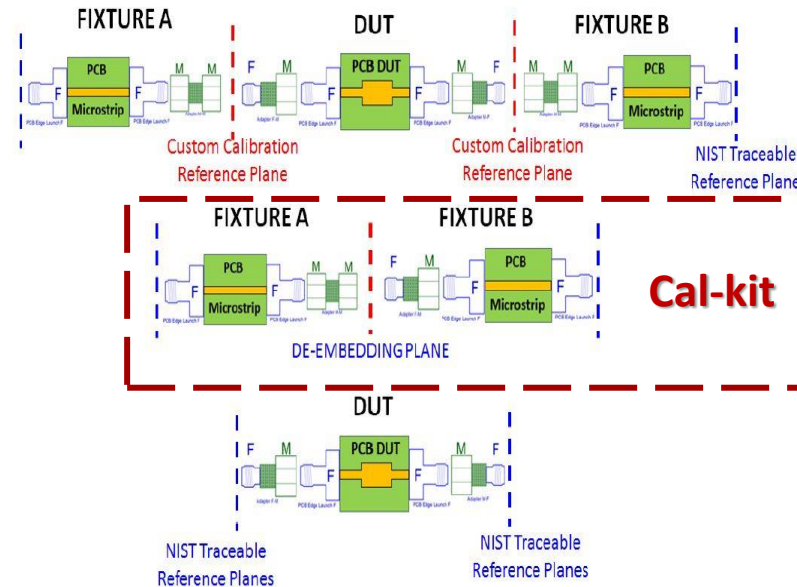


Figure 38: Setup example picture for measuring the DUT.

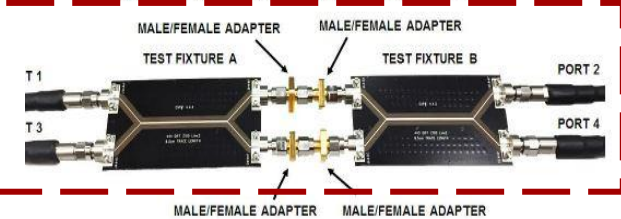


Figure 39: Setup example picture for measuring the test fixture 2x-thru.

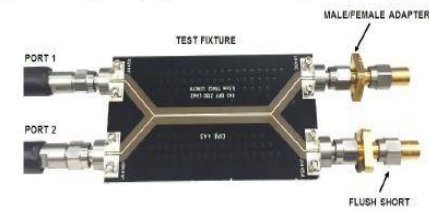


Figure 40: Setup example picture for measuring the open/short 1x-reflect (short on the picture).

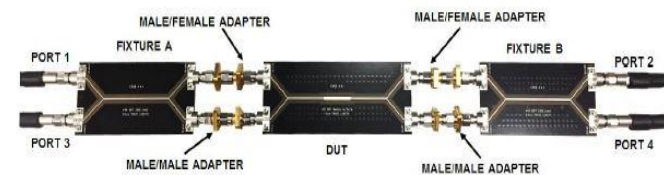


Figure 41: Setup example picture for measuring the DUT plus the test fixture.

$$T_{\text{total}} = [T_{\text{Fixture}_A}] \times [T_{\text{DUT}}] \times [T_{\text{Fixture}_B}]$$

$$T_{2X} = [T_{\text{Fixture}_A}] \times [T_{\text{Fixture}_B}]$$

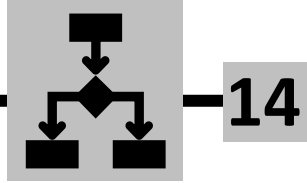
$$T_A = \text{FixtureRemovalAlgorithm}(T_{2X})$$

$$T_{\text{DUT}} = [T_{\text{Fixture}_A}]^{-1} \times [T_{\text{total}}] \times [T_{\text{Fixture}_B}]^{-1}$$

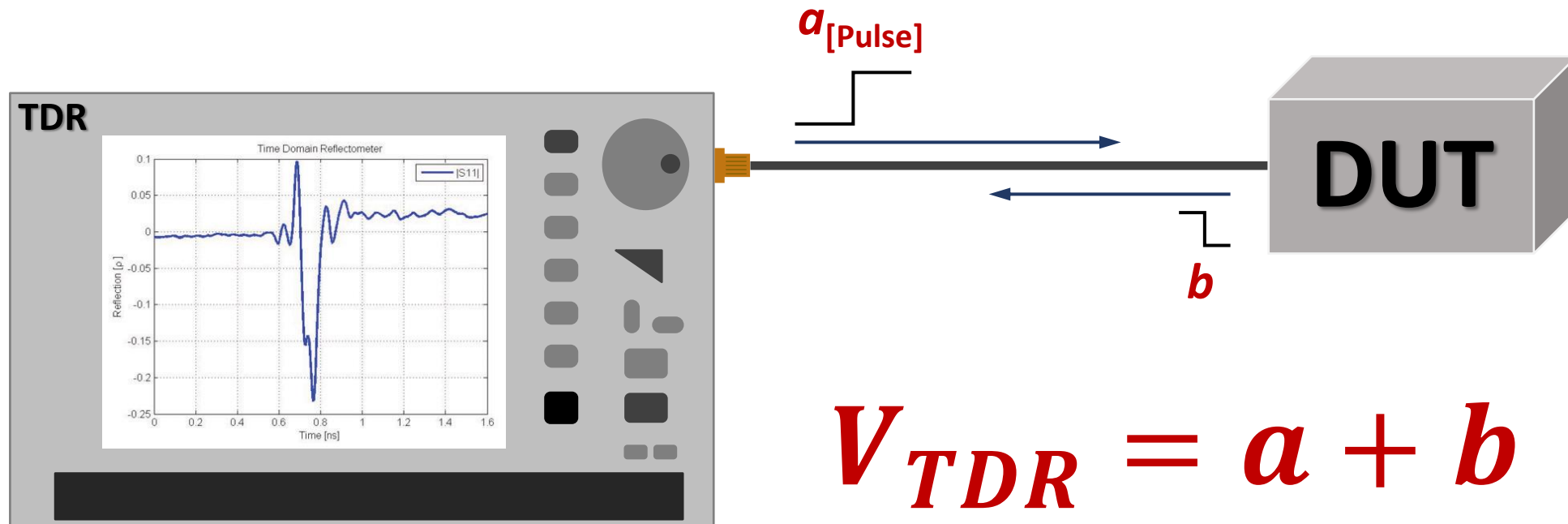
Automatic Fixture Removal (AFR)

Smart Fixture De-embedding (SFD)

Time Domain Reflectometer (TDR)

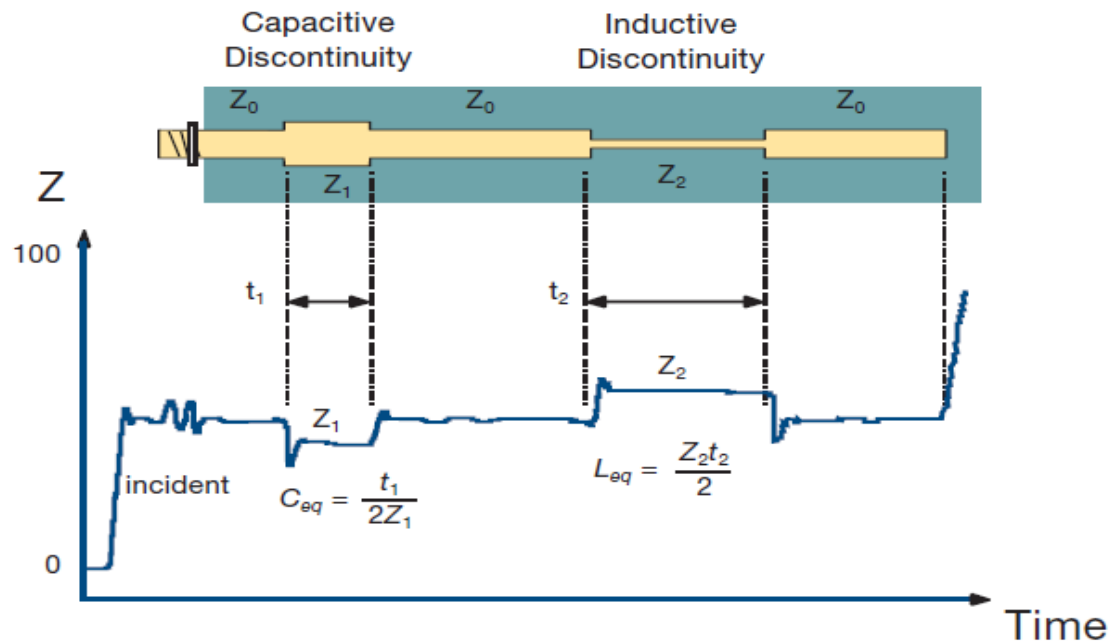
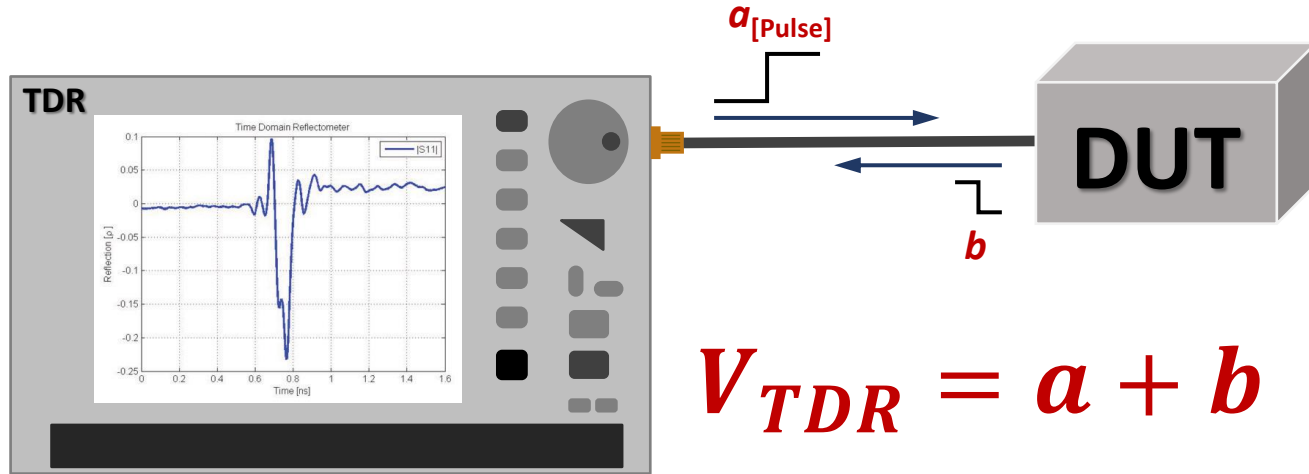


- ❑ An instrument used to determine the characteristics of transmission line by observing the **reflected waveforms**

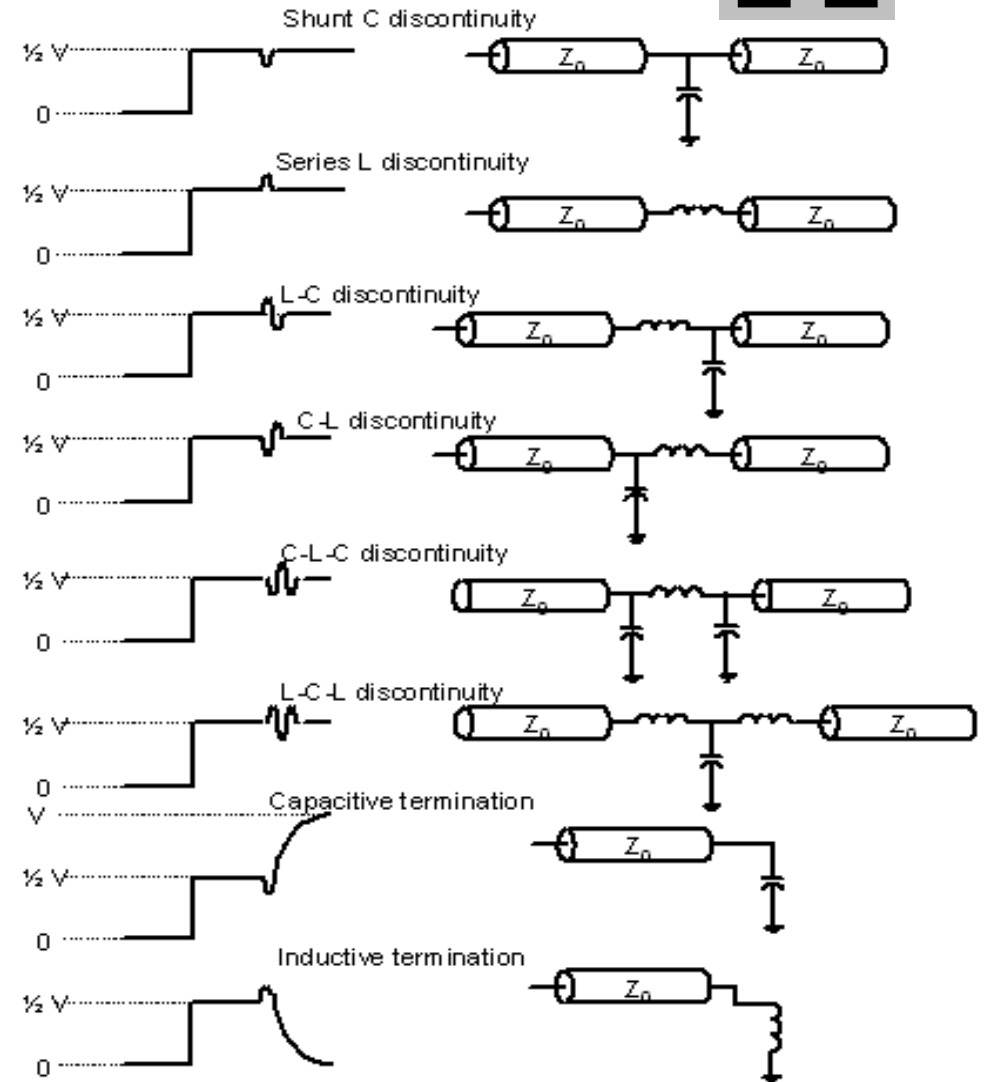


Time Domain Reflectometer (TDR)

15

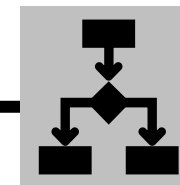


"www.protoexpress.com"



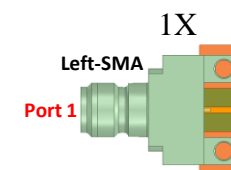
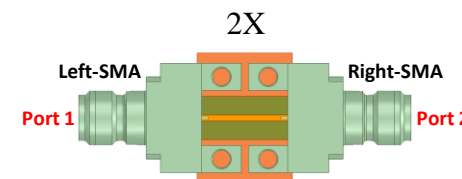
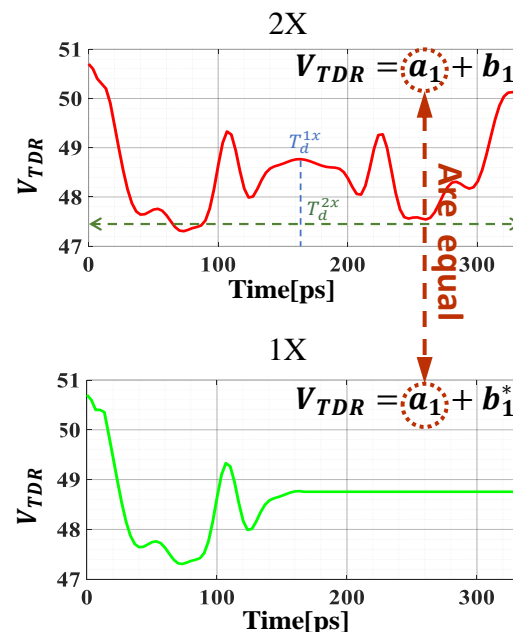
"EETimes"

The Time Domain to Separate 2X(TDR)



16

1. Determine the middle time of the 2x-thru.
2. Extract the impedance of the 2x-thru at the middle using the TDR or $\text{ifft}(S_{11})$.
3. Renormalize the 2x-thru from the reference impedance of the S-parameters to the measured impedance of the transmission line from step 2 (2x-thru) to satisfy Equation ($Z_{\text{Left}_F} = Z_{\text{Right}_F}^*$).
4. Extrapolate the DC point of S_{11} .
5. Convert the half-spectrum domain data into full frequency domain data by enforcing symmetry.
6. Convert the symmetric information to the time domain.
7. Shift the time-domain data right by n points (where n = number of frequency points of S_{11}).
8. Make all discrete points of the resultant time-domain data zero from the middle point to the end.
9. Shift the time-domain data left by n points.
10. Convert the time-domain data to frequency domain.
11. Discard all content at negative frequencies.
12. Repeat steps 2 through 11 for S_{22} .



2x thru TDR

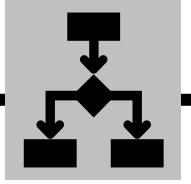
Cutting TDR of
2xthru in Half

$$T_{d1x} = \frac{T_{d2x}}{2}$$

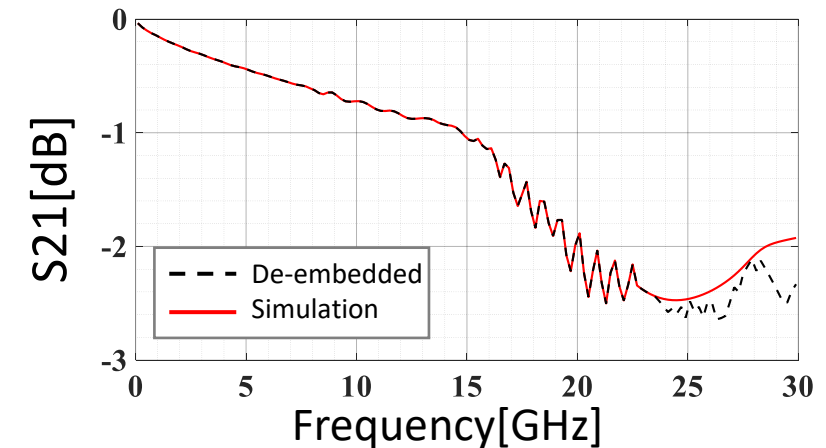
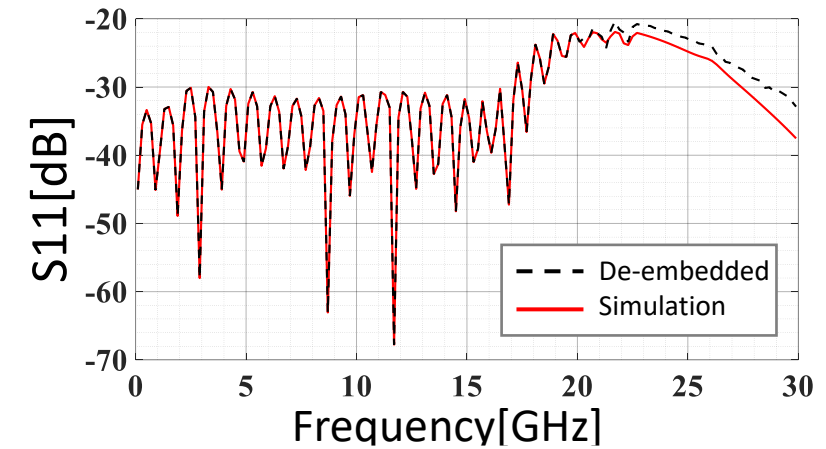
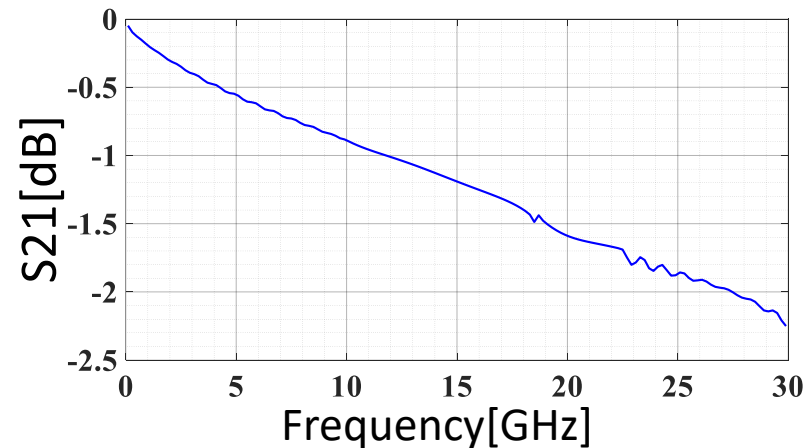
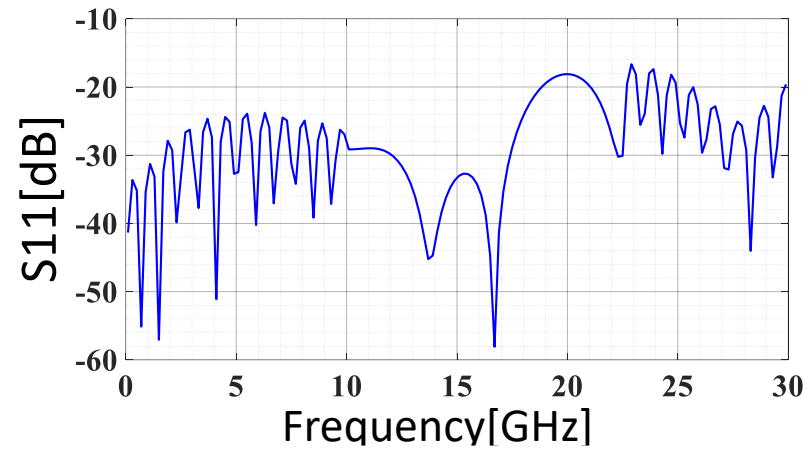
1X Fixture TDR

$S_{11}^{1x} = \frac{\text{fft}(b_1^*)}{\text{fft}(a_1)}$	$S_{21}^{1x} = S_{12}^{1x}$	$S_{22}^{1x} = \frac{S_{11}^{2x} - S_{11}^{1x}}{S_{21}^{2x}}$
$S_{22}^{1x} = \frac{\text{fft}(b_2^*)}{\text{fft}(a_2)}$	$S_{21}^{2x} = S_{12}^{2x}$	$(S_{21}^{1x})^2 = (1 - (S_{22}^{1x})^2) \times S_{21}^{2x}$

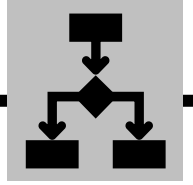
The 2X Thru De-embedding Results



17



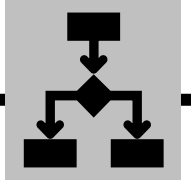
The 2X Thru Weaknesses



18

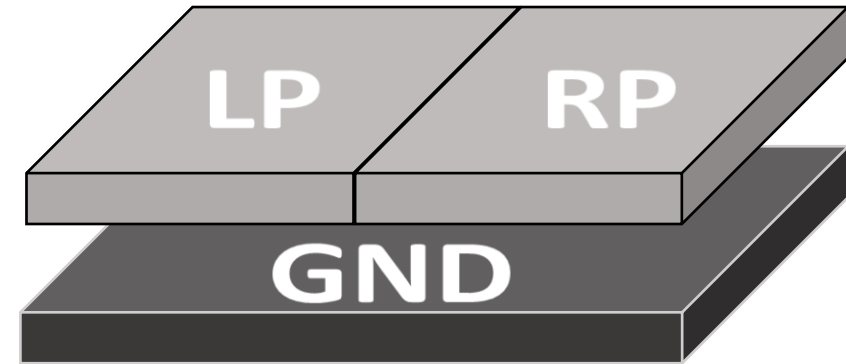
- ❑ For designing **2x thru structure** the fixtures which are **vertical** cannot be connected directly.
- ❑ It is impossible to build the correct **TDR waveform** for the 1x-fixture when there is a discontinuity at the end of the 1x fixture. **If the impedance at the middle point is 50Ω , the measured reflection ratio is equal to the return loss.**
 - This problem can be solved by adding a **50Ω transmission line which is long enough between 1x fixtures in 2x thru.**

Separation of $[T_{LS}]$ and $[T_{RS}]$ from Each Other



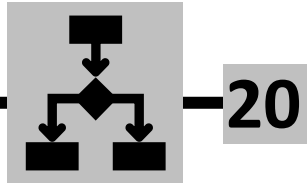
19

$$T_{\text{thru}} = [T_{LS}] \times [T_{RS}]$$



Large Scale

The Time Domain to Separate T_{Thru}



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- I. Conversion of the T-parameters (T_{Thru}) to the S-parameters (S_{Thru})
- II. Conversion of S_{11}^{Thru} from frequency domain to time domain by *ifft* transform.

$$S_{11}^{\text{Thru}}(t) = \mathcal{F}^{-1} \{S_{11}^{\text{Thru}}(f)\}$$

- III. Determine the midpoint of $S_{11}^{\text{Thru}}(t)$ response and extract impedance in the midpoint.

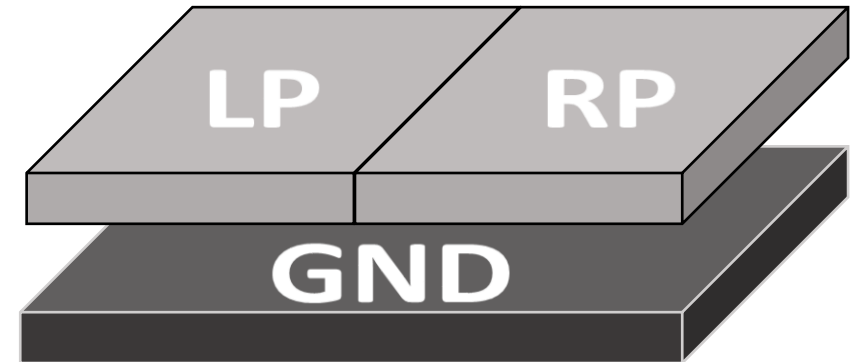
- IV. Convert the half-spectrum domain data into full frequency domain data by enforcing symmetry.
- IV. Or can replace the right half-spectrum of time domain response by the midpoint.

- V. Convert the time domain data to frequencies by *fft*.

$$S_{11}^{\text{LS}}(f) = \mathcal{F}\{S_{11}^{\text{LS}}(t)\}$$

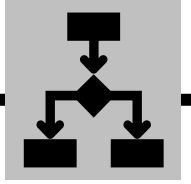
- VI. Convert the S-parameter of left-structure to T-parameter

$$T_{\text{thru}} = [T_{\text{LS}}] \times [T_{\text{RS}}]$$

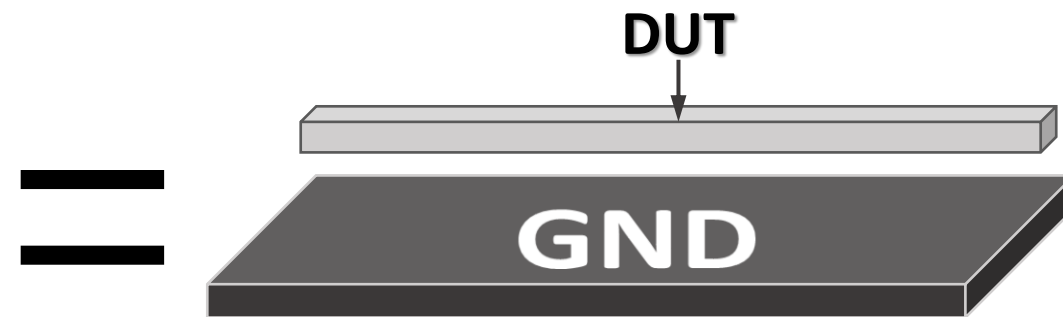
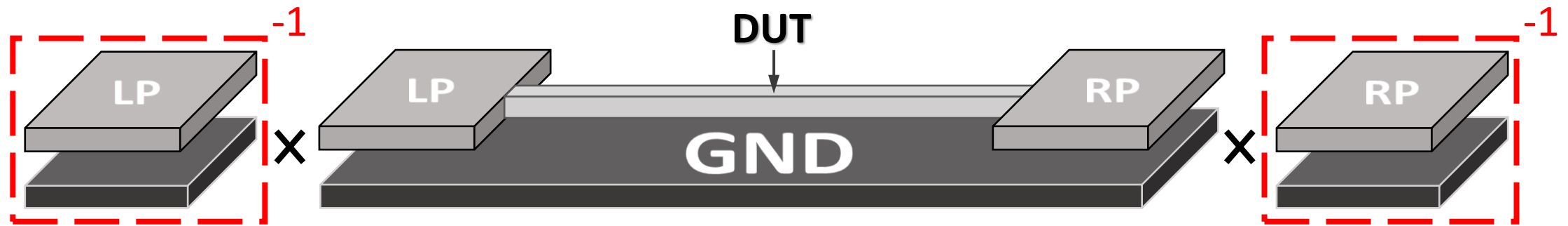


$S_{12}^{\text{LS}} = S_{21}^{\text{LS}}$	$S_{22}^{\text{LS}} = \frac{S_{11}^{\text{Thru}} - S_{11}^{\text{LS}}}{S_{21}^{\text{Thru}}}$
$S_{21}^{\text{Thru}} = S_{12}^{\text{Thru}}$	$S_{21}^{\text{LS}^2} = (1 - S_{22}^{\text{LS}^2}) \times S_{21}^{\text{Thru}}$

De-embed of the DUT structure



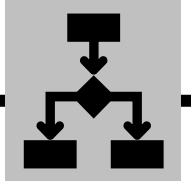
21



$$[T_{DUT} = [T_{LS}]^{-1} \times [T_{2L}] \times [T_{LR}]^{-1}]$$

Convert T-parameters of DUT to the S-parameter

The Structures That Can be De-embedded



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PCB's Bump



PCB's Differential Structure

Condition

The Structures must be symmetrical

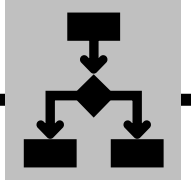


PCB's Vias



SMA Connectors

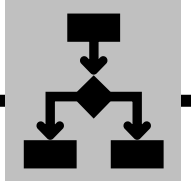
Advantage of the Proposed Method



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- ✓ This method can be used for any structure including **vertical** and **horizontal**.
- ✓ No need a **matching midline** to extract the S_{11} time response.

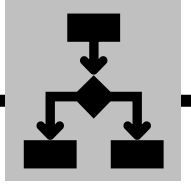
Weakness of the Proposed Method



24

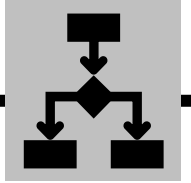
- ✗ To perform **this method**, we need **two test structures** that are more **complex than** designing a calibration kit for **2x Thru de-embedding**.
- ✗ The **test structure** must be **symmetrical**.

Conclusion



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- ❖ We saw that the a method has a **potential to de-embed PCB's Structures**.
- ❖ The calibration-kits of the proposed method are **simpler than TRL and SLOT methods** and are more **complex than 2x Thru**.
- ❖ The method could be used for de-embedding any **symmetrical structures** (on the PCB).
- ❖ The method has **advantages and disadvantages compared to 2x thru**.



- **De-embedding simplest test structure** ([Pad].[Line].[pad]) using proposed L-2L de-embedding method.
- Designing a **GUI program** (tool) for the L-2L method using **Python** similar to other powerful tools such as:
 - 2X Thru AFR
 - AICC
 - AITT-AR
 - EMStar
 - [IEEE Standards Association / Elec Char / P370 · GitLab](#)

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Thank you